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Dielectric properties and electrical conduction of high-k LaGdO<sub>3</sub> ceramics<sup>1</sup> SHOJAN PAVUNNY, REJI THOMAS, ASHOK KUMAR, RAM KATI-YAR, Department of Physics and Institute for Functional Nanomaterials, University of Puerto Rico, San Juan, PR, USA — The temperature and frequency dependent dielectric properties and leakage conduction mechanism in LaGdO<sub>3</sub> (LGO) ceramics have been studied and this material has been identified as a potential high-k candidate for the future complementary metal-oxide-semiconductor (CMOS) and dynamic random access memory (DRAM) technology nodes. The dielectric constant and the loss tangent at 100 kHz were  $\sim 21.5$  and  $\sim 0.003$  respectively at ambient conditions without any significant temperature and voltage dependence. The ac conductivity showed the typical features of universal dynamic response (UDR) and obey the double power law  $\sigma_{ac} = \sigma_{dc} + A\omega^{n_1} + B\omega^{n_2}$  with three types of temperature dependent conduction processes involved; i) a dc plateau (< 3 kHz) due to long range translational hopping, ii) a mid frequency region due to the short range hopping (3 - 100)kHz), and iii) a high frequency region due to localized or reorientational hopping (100 - 1000 kHz). The temperature dependent dc conductivity followed the Arrhenius relation with activation energies of 0.05 eV in the 200 - 400 K range and 0.92eV in the 400 – 600 K range. The leakage current behavior revealed bulk limited Poole-Frenkel (PF) conduction mechanism with very low leakage current density (2 nA /  $cm^2$  at 5.7 kV/cm).

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